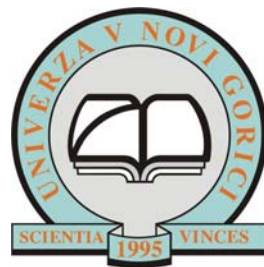


Initial Stages of Growth of Organic Semiconductors on Graphene

Presented by:
Manisha Chhikara

Supervisor: Prof. Dr. Gvido Bratina



University of Nova Gorica

Outline

- **Introduction to Graphene**

 - Fabrication

 - Characterization: AFM (Atomic Force Microscope)

 - Properties: Electronic, Optical

 - Applications

- **Growth of organic semiconductors (OS) on Graphene**

 - OMBD (Organic Molecular Beam Deposition)

 - Growth Modes: Types

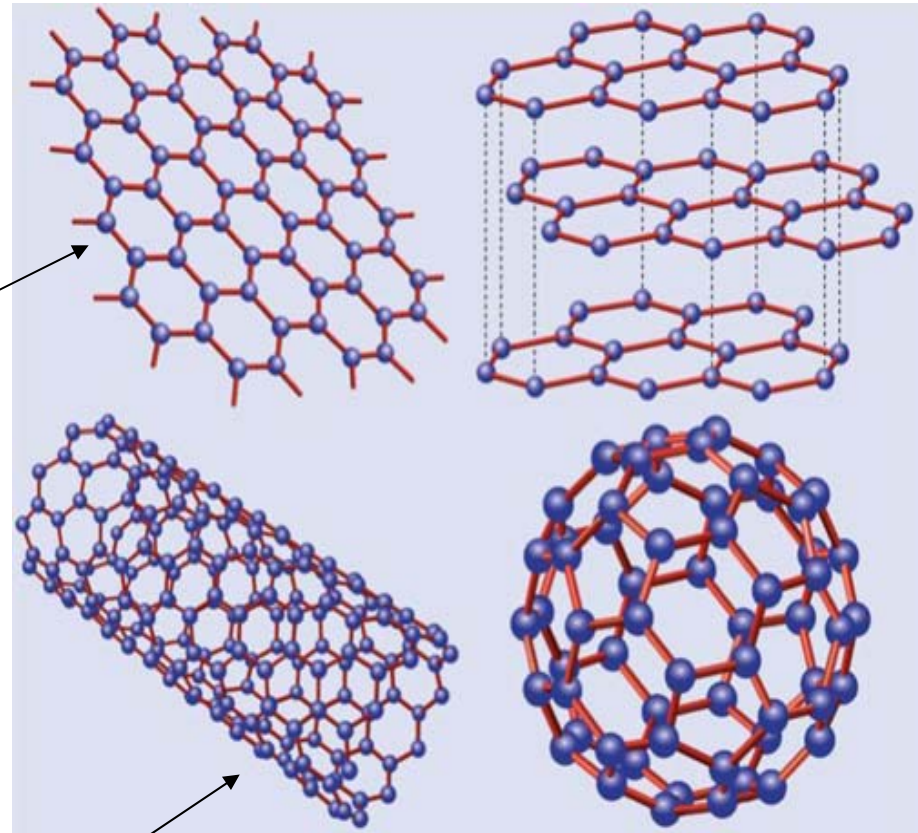
- **Conclusions**

Introduction to Graphene

- Hexagonal arrangement of carbon atoms forming an atom thick planar sheets
- C-C bond $\sim 1.42 \text{ \AA}$
- Thickness of one atomic layer $\sim .34\text{nm}$ (\sim layer spacing of graphite)
- Strong
- Flexible
- High intrinsic carrier mobility $\sim 200000 \text{ cm}^2/\text{Vs}$
- High thermal conductivity

Graphite

Graphene

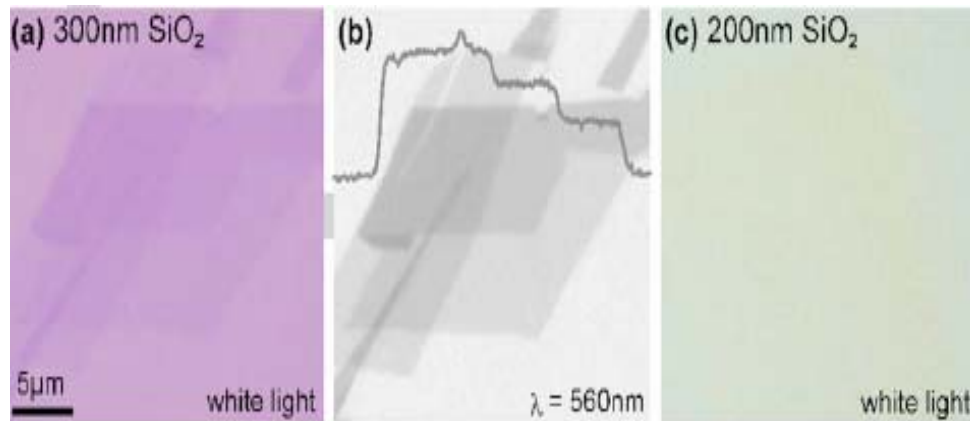
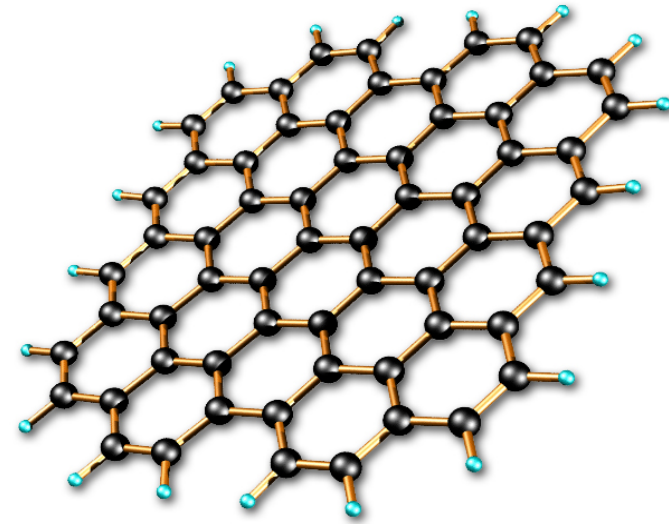


Carbon nanotubes

Fullerene

Late discovery of Graphene

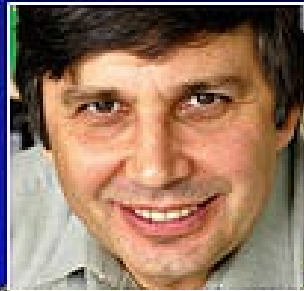
- **Discovered in 2004**
- Graphene monolayer in great minority among thicker flakes
- Unlike nanotubes, no clear signature by TEM
- Completely transparent on most of substrates
- The only method: AFM
very low throughput at high resolution



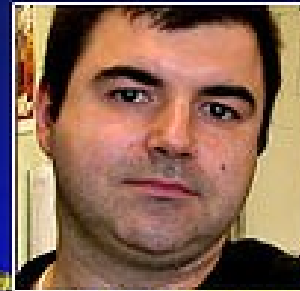
200μm

The Nobel Prize in Physics 2010

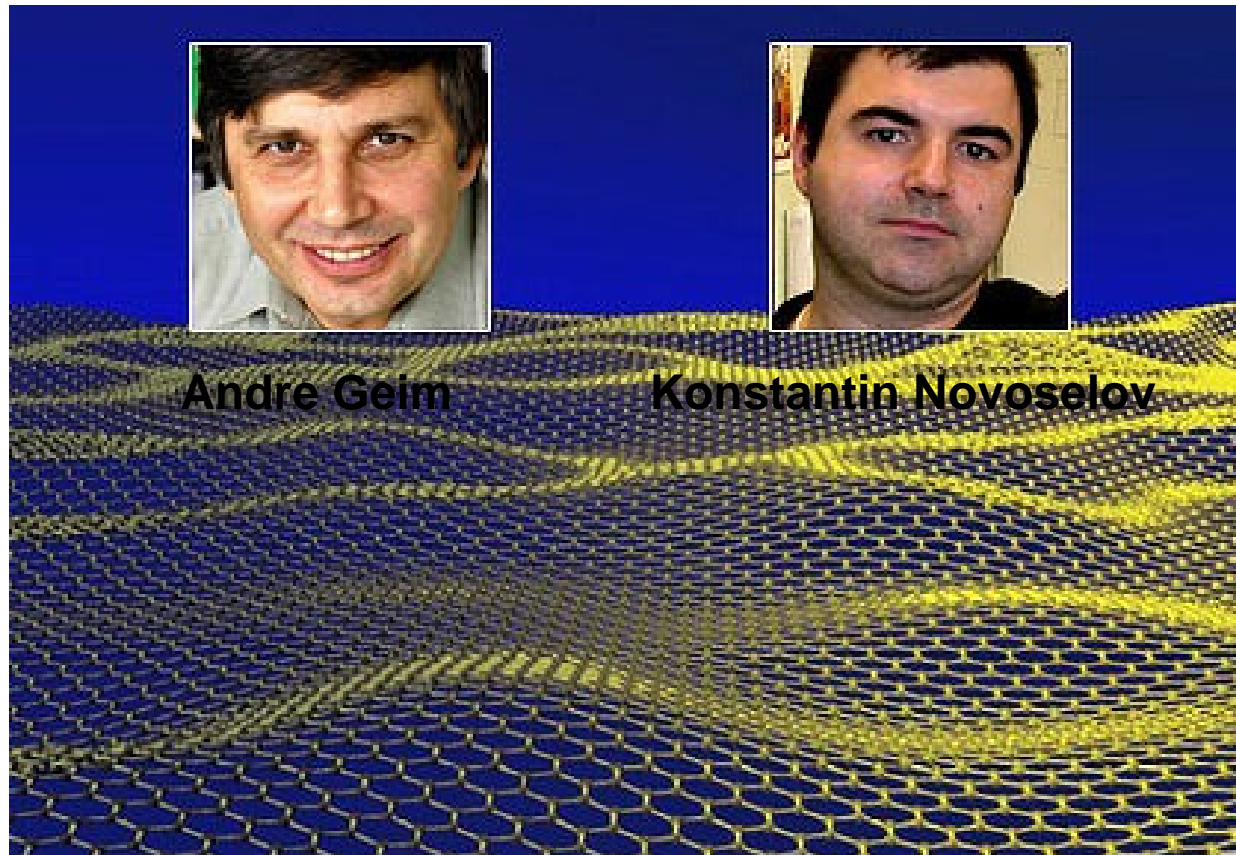
“Graphene”



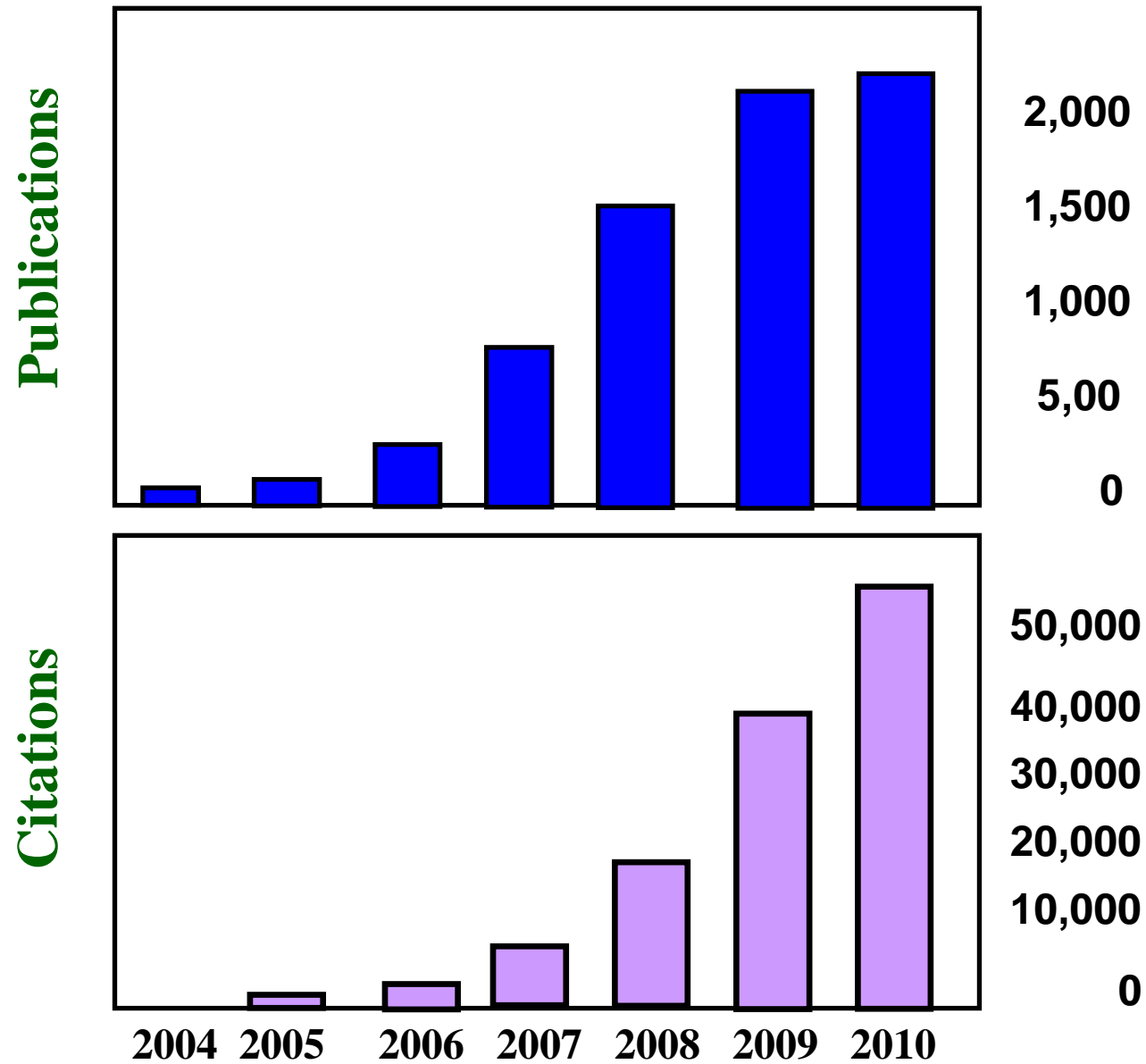
Andre Geim



Konstantin Novoselov



Impact of graphene in Scientific community



Fabrication Methods: Mechanical exfoliation

Advantages:

Cheap

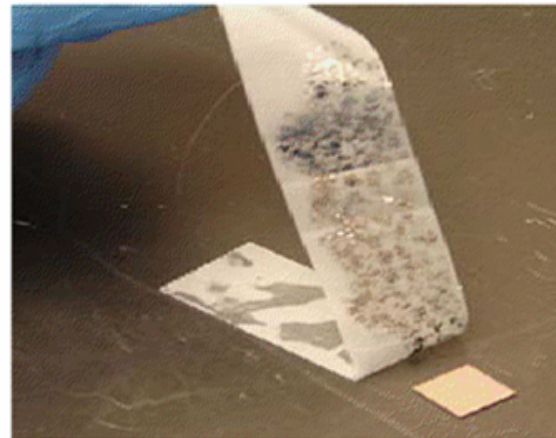
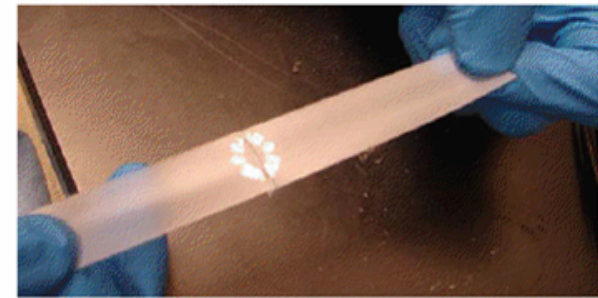
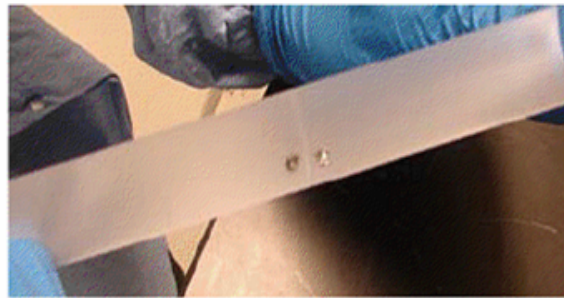
Limitations:

Limited to small area

Many uneven films

Time consuming

Peel off technique



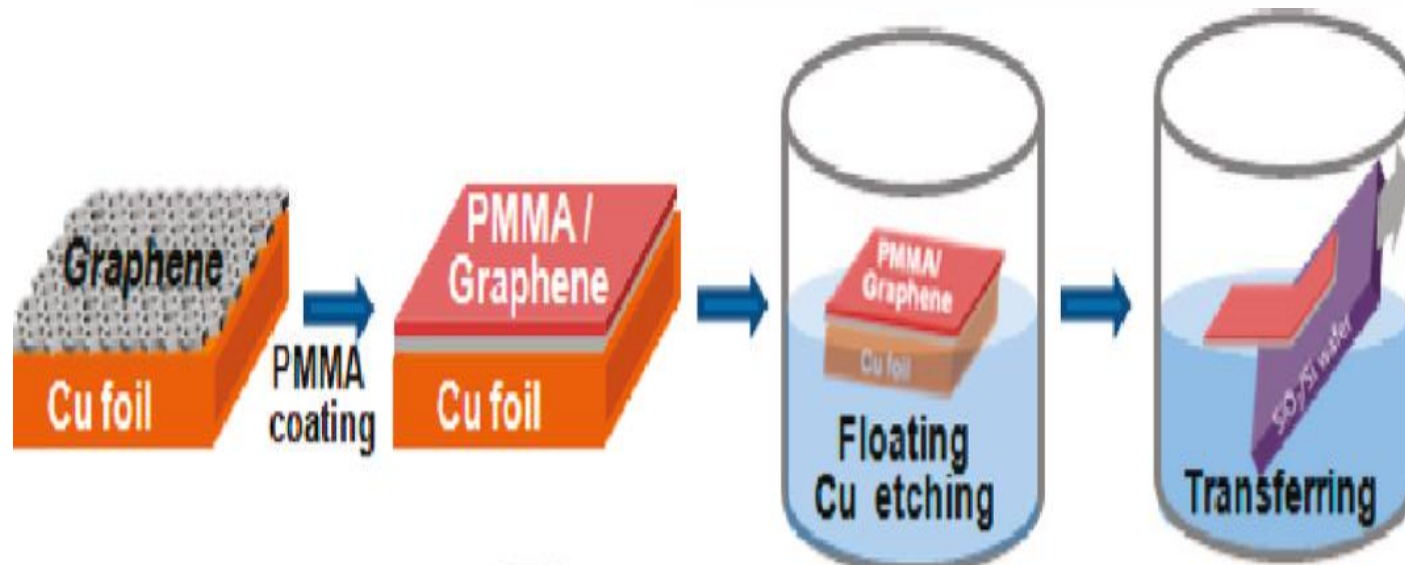
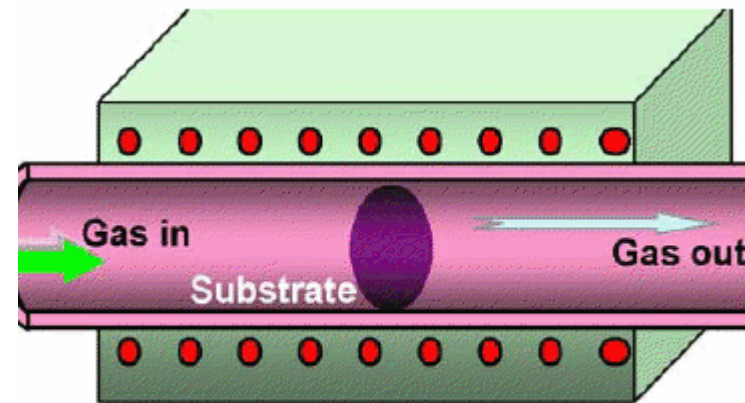
Chemical vapor deposition (CVD) method

Advantages:

- Great technique for large area graphene
- Requires less labor
- Continuous films

Limitation:

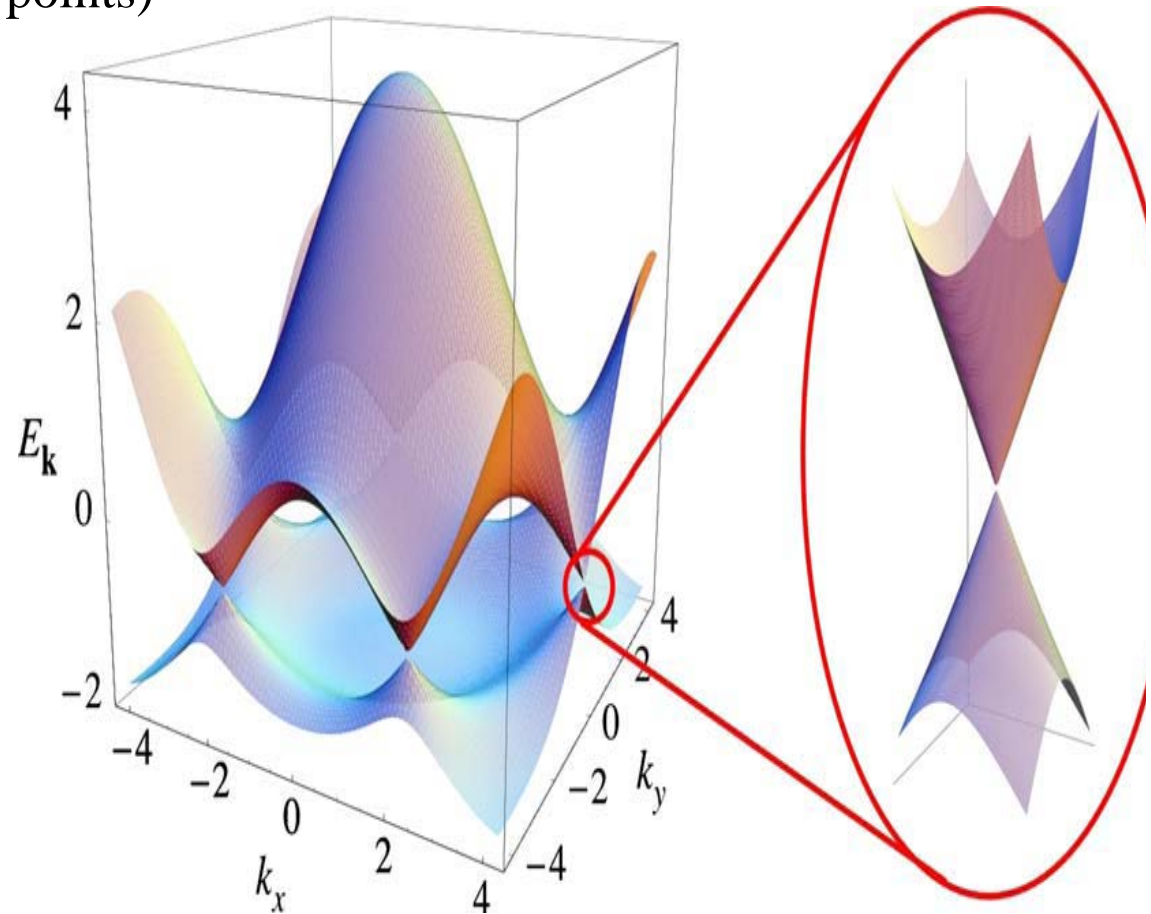
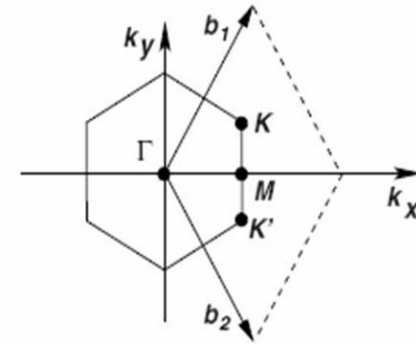
- Require high temperature



Band Structure of graphene

The spectrum is described by the tight-binding Hamiltonian on a hexagonal lattice

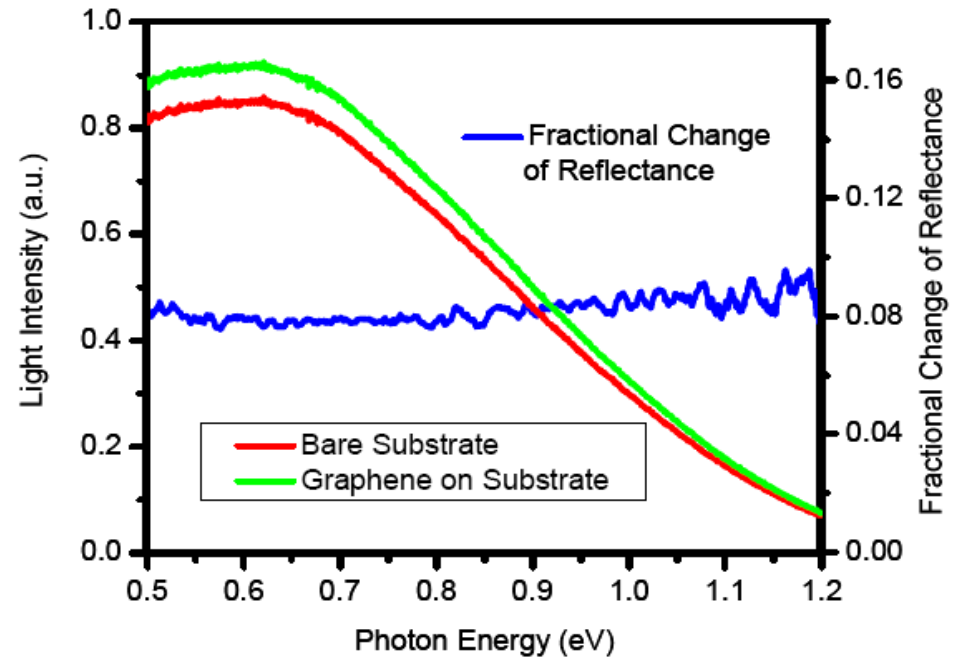
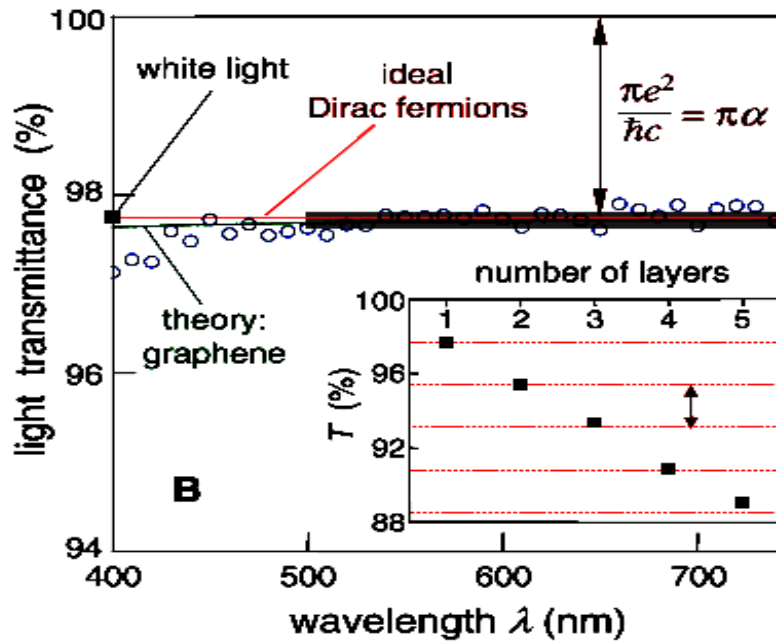
- Band crossing at K and K' (Dirac points)
- Dispersion is similar to that of relativistic particles, $E = \hbar v_F k$
- Fermi velocity $v_F = 10^6$ m/s
- Zero band gap semiconductor
- Charge carriers ~ massless Dirac Fermions



Optical properties of graphene

Absorption of light by 2D Dirac fermions

- Graphene absorbs $\pi\alpha \approx 2.3\%$ of white light, where α = fine structure constant
- Transmission, $T = 1 - \pi\alpha$, Reflection, $R \ll 1$

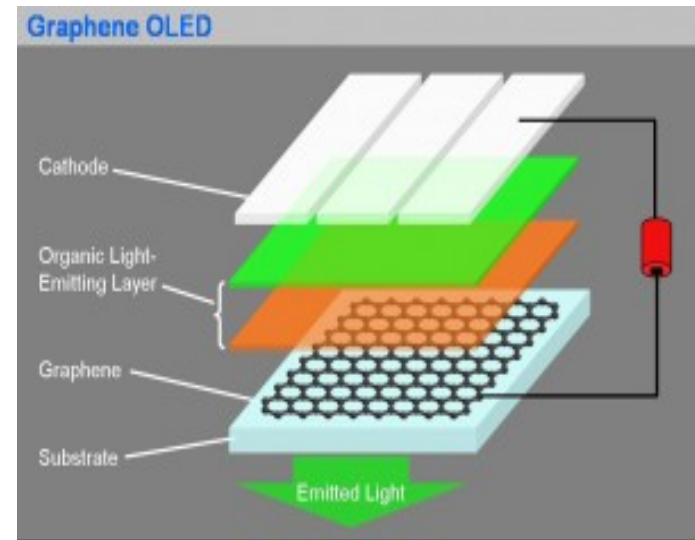
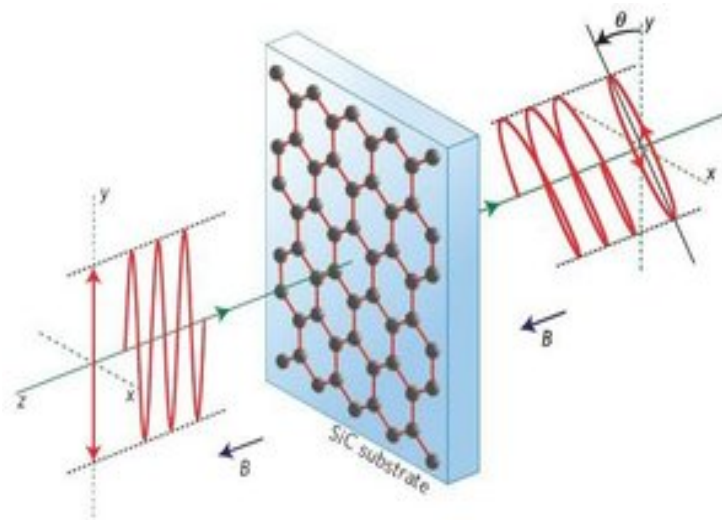


Possible applications of graphene

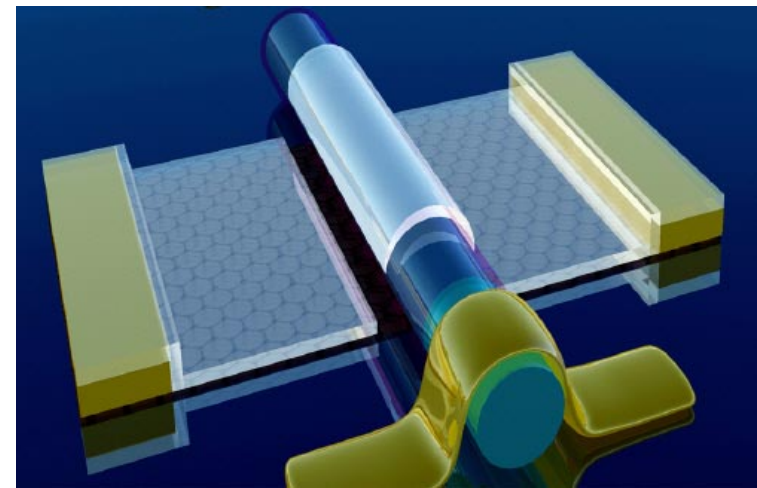
- TCO (Transparent conducting electrode)
Alternative to ITO (expensive, difficult to recycle)

Electrode very thin (couple of nm thick)

Compatible with large scale manufacturing methods
- Can be used to polarize light
- Saturable absorber



Graphene Transister



Characterization of graphene

AFM (Atomic Force Microscope)

- Used to characterize the surfaces on nanometer scale

The force acting on the cantilever,

$$F = -kz$$

k = spring constant of cantilever

z = deflection of cantilever

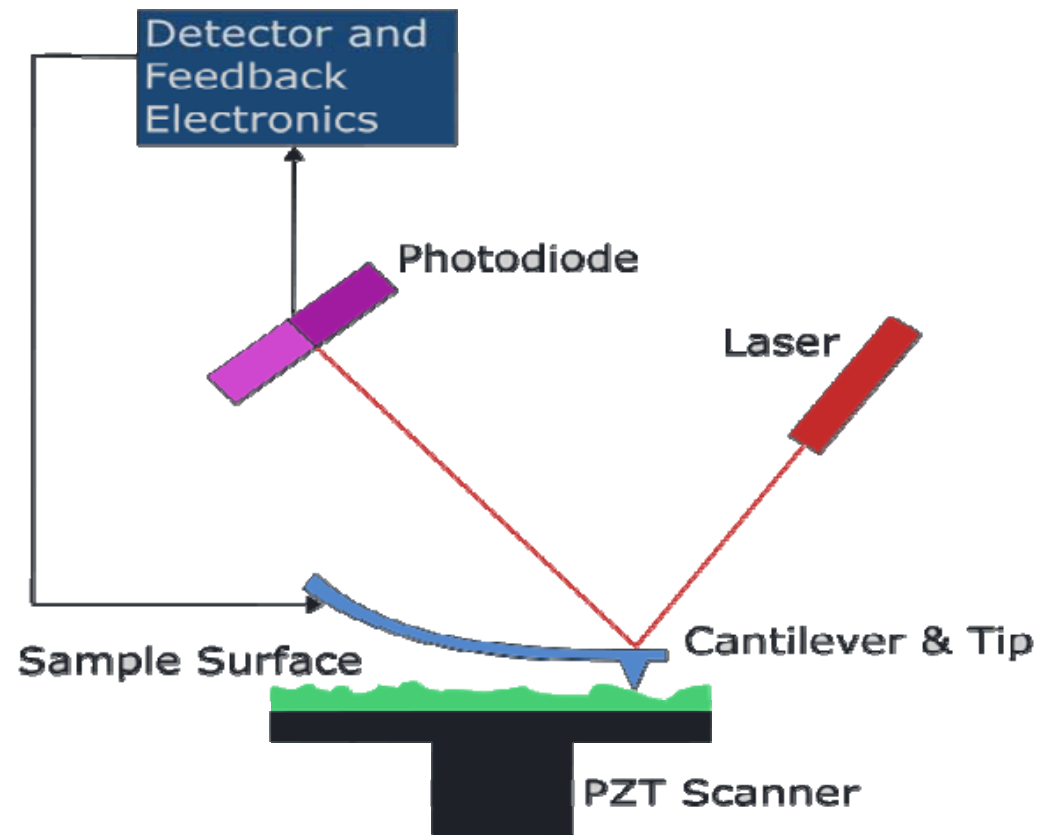


Fig. Scheme illustrating the working of AFM

Operating modes

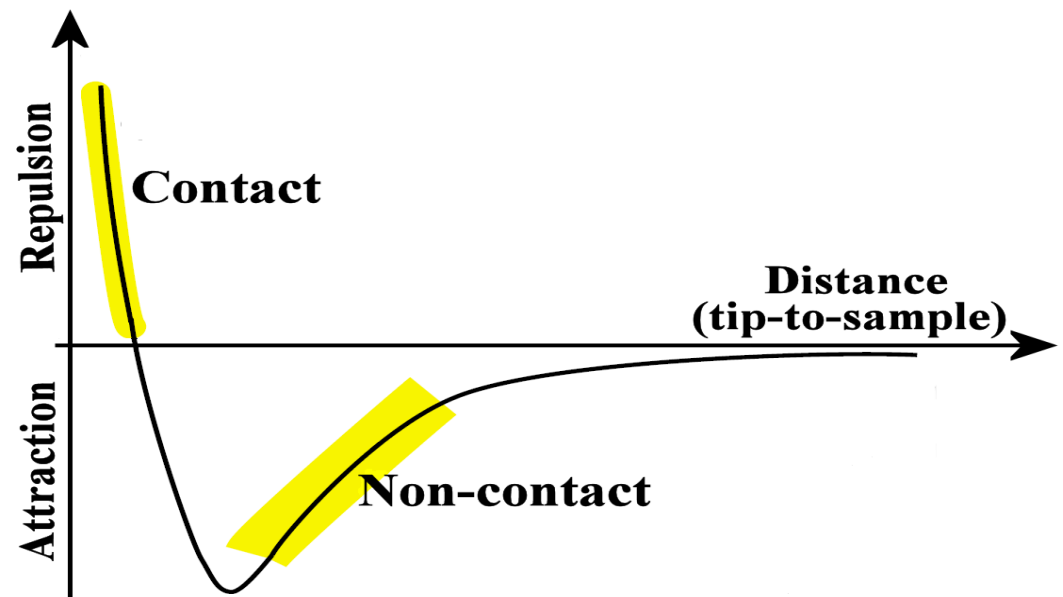
Contact mode

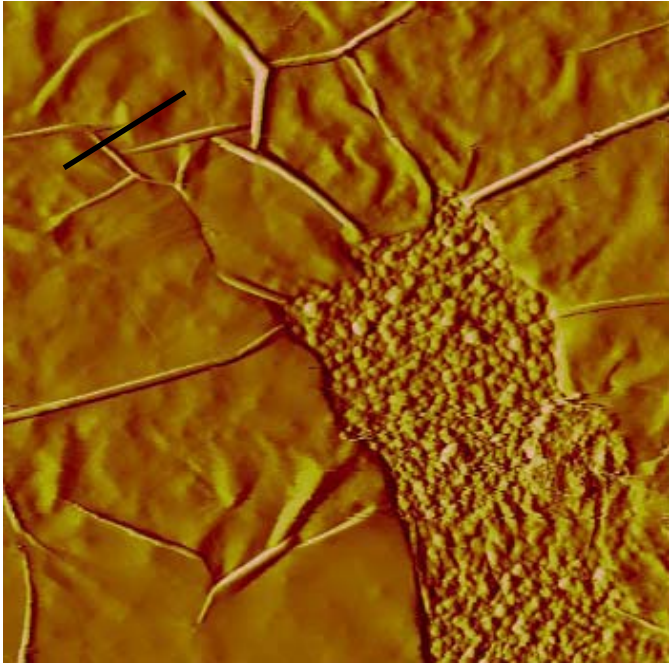
- $S \sim \text{few nm}$
- $F \sim 10^{-8} \text{ to } 10^{-6} \text{ N}$
- High resolution

Non-contact mode

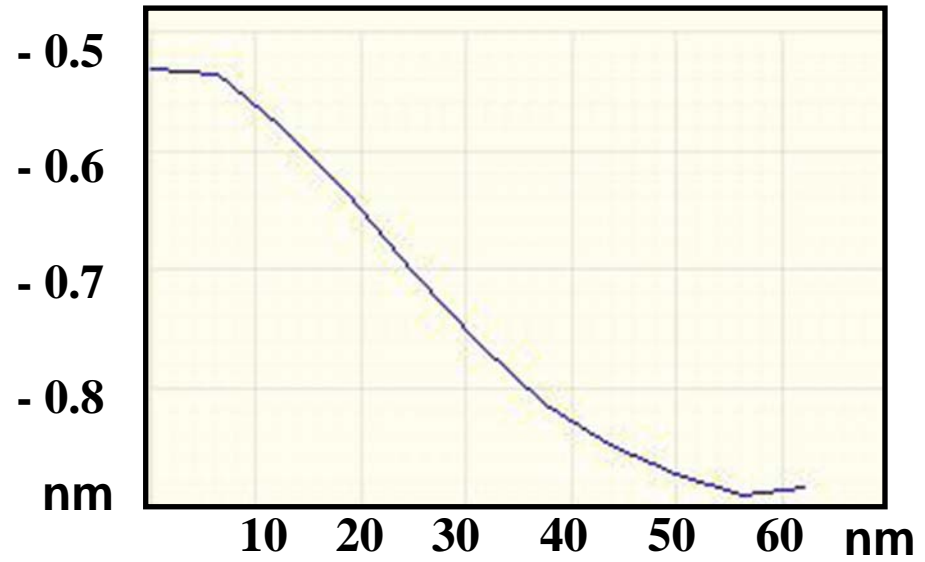
- $S \sim 10 \text{ nm}$
- $F \sim 10^{-12} \text{ N}$
- Suitable for soft samples

S = distance between tip and surface
 F = force between tip and surface





AFM image of graphene

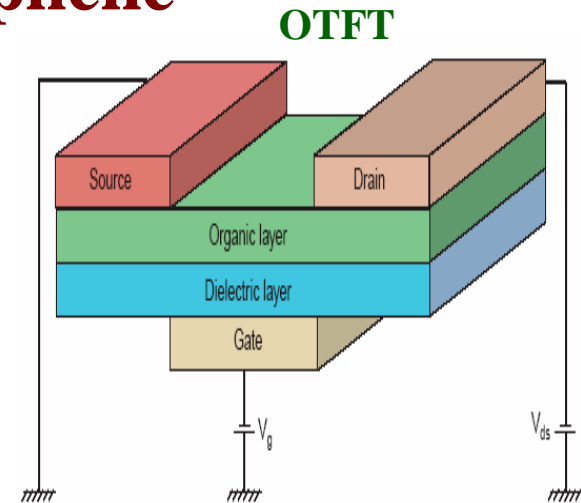


~0.35 nm

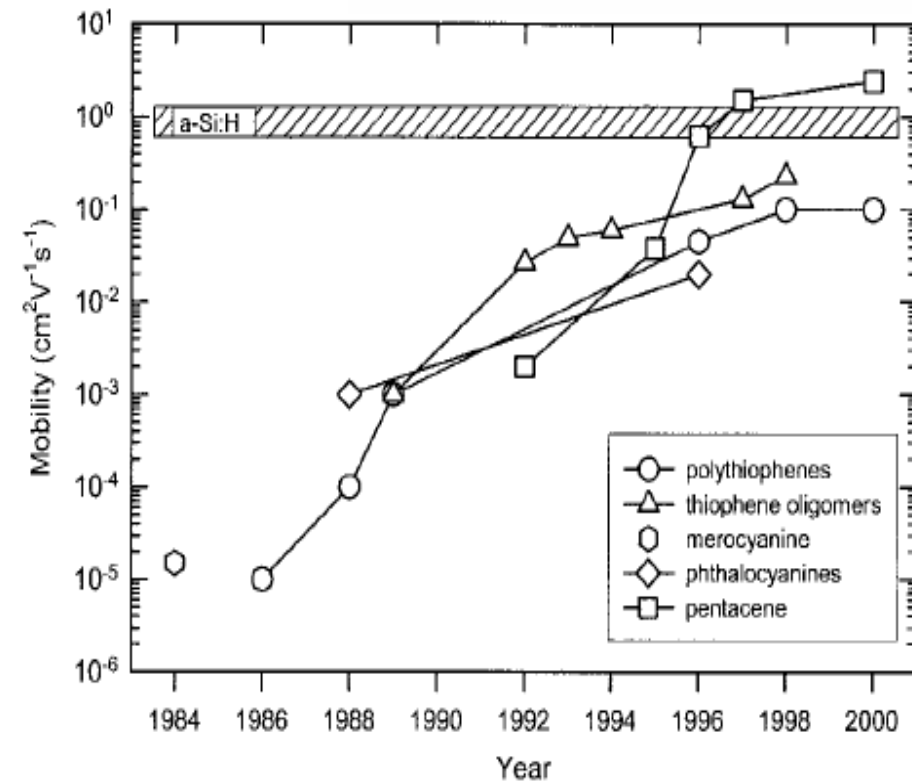
AFM measurement across a wrinkle confirming interlayer spacing of ~0.35 nm.

Growth of OS on graphene

- Low cost, mechanically flexible, easy to fabricate
- Aspects of interface
 - Organic Solar cell, OLEDs, OTFTs

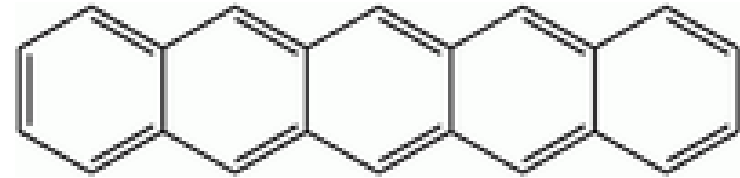


- Pentacene-based organic thin film transistors (OTFTs) reached charge carrier mobility of the order of $1 \text{ cm}^2/\text{Vs}$
- Graphene can be used as a substrate



Pentacene

- Crystal structure - **Triclinic**
- Band gap - **2.2eV**
- High carrier mobility
- Excellent interface properties with organic materials
- Form highly ordered organic films



Structural formula of Pentacene

Organic Molecular Beam Deposition

- The growth is controlled with the precision of a single molecular layer

- **Generation of the molecular beam**
- **Mixing zone**
- **Growth on substrate**

Sticking coefficient,

$$s = N_{\text{adh}} / N_{\text{tot}}$$

N_{adh} = no. of atoms adhering to substrate

N_{tot} = no. of atoms arriving

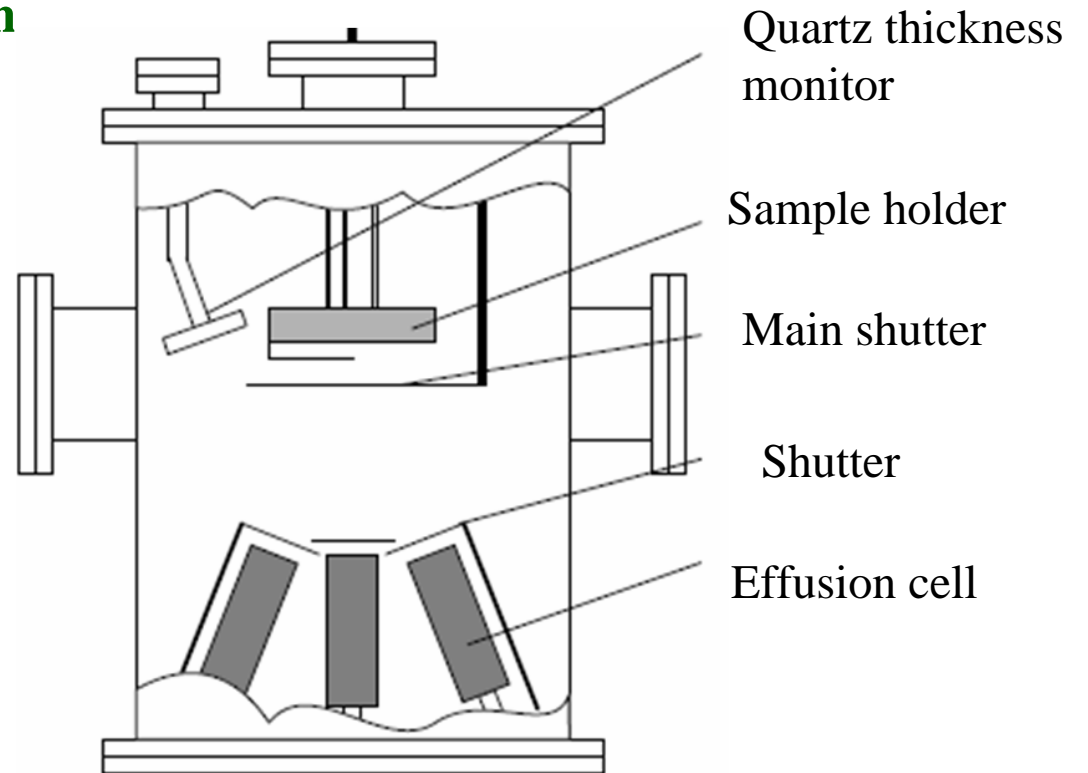
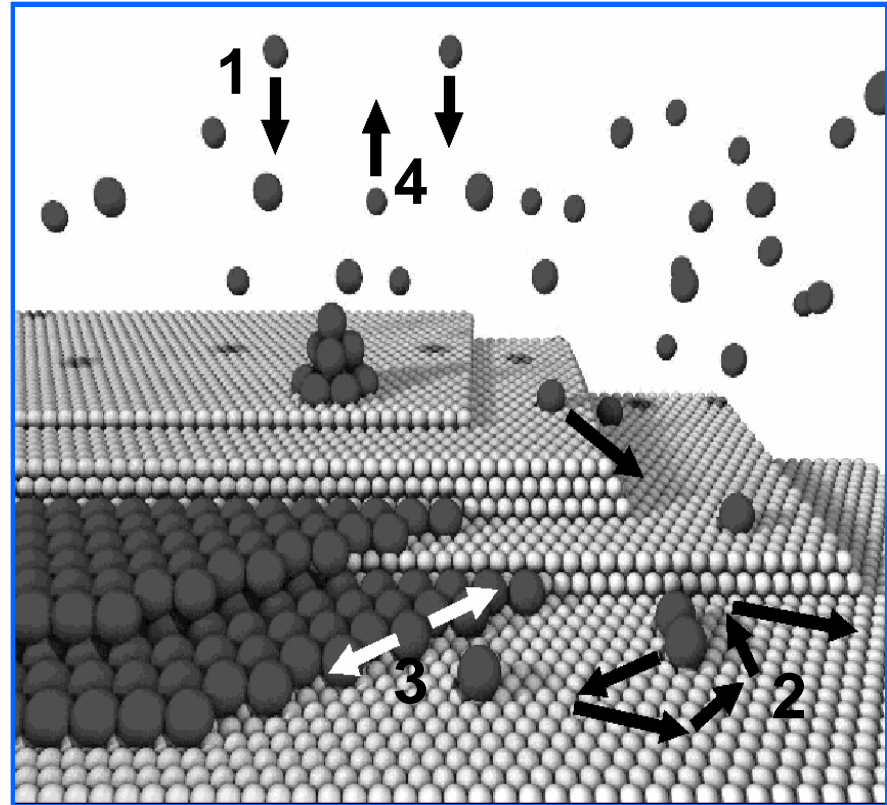


Fig. Organic Molecular Beam Setup

Practically, $s < 1$

A series of process occur

- 1) Adsorption of atoms or molecules impinging on substrate surface
 - a) Physical adsorption- no electron transfer
 - b) Chemical adsorption-electron transfer
- 2) Surface migration and dissociation of adsorbed molecules
- 3) Incorporation of constituent atoms into crystal lattice
- 4) Desorption



Structure of organic films grown depends upon

- Type of molecule/substrate interaction

Layer-by-layer (Frank van der Merwe) growth mode

if molecule/substrate interaction $>$ intermolecular interaction

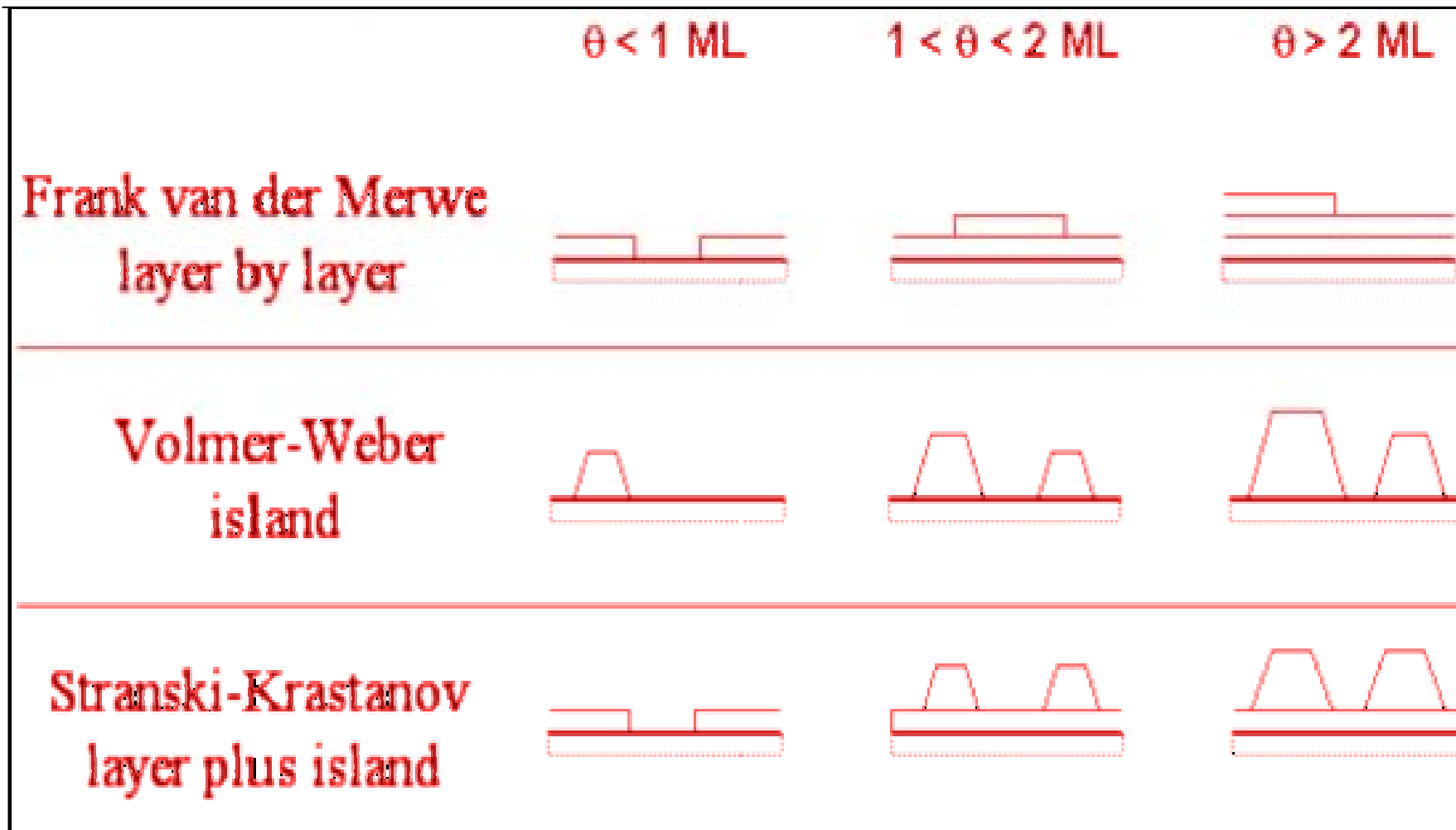
Layer-plus-island (Stranski- Krastanov)- intermediate mode

layer growth unfavorable after first few layers

Islands (Volmer- Weber growth mode)

if intermolecular interaction $>$ molecule/substrate

- Substrate temperature
- Density of surface defects
- Surface energy



J. A. Venables et. al, Rep. Prog. Phys 47, 399 (1984)

Density of islands depends upon

- Deposition rate
- Substrate temperature and described as power law

$$N = R^p e^{\left(\frac{E_{\text{nucl}}}{K_B T_s}\right)}$$

p = critical exponent, K_B = Boltzmann constant

E_{nucl} = activation energy for homogenous nucleation

- a) Surface diffusion (E_d)
- b) Desorption from substrate surface (E_a)
- c) Formation of island of critical size i with binding energy E_i

Specific issues to organic thin film growth

- **Internal degrees of freedom**

Orientational degrees of freedom-orientation domain

Vibrational degrees of freedom-impact on interaction with surface

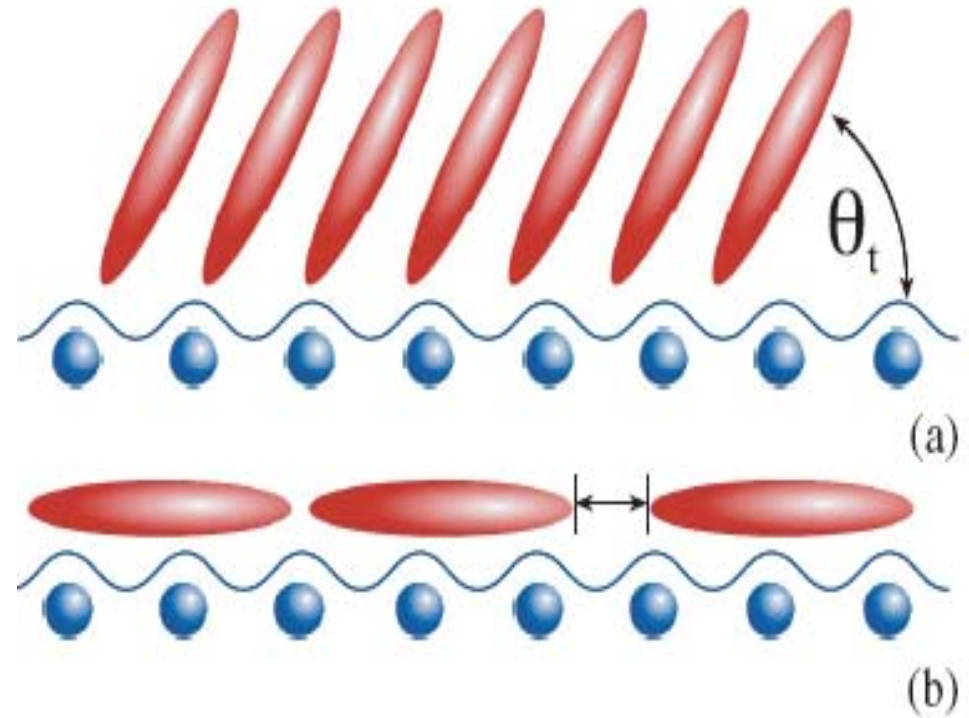
- **Interaction potential**

(Molecule-molecule and molecule-substrate)

Strongly interacting surface-limited diffusion

- **Size of the molecules**

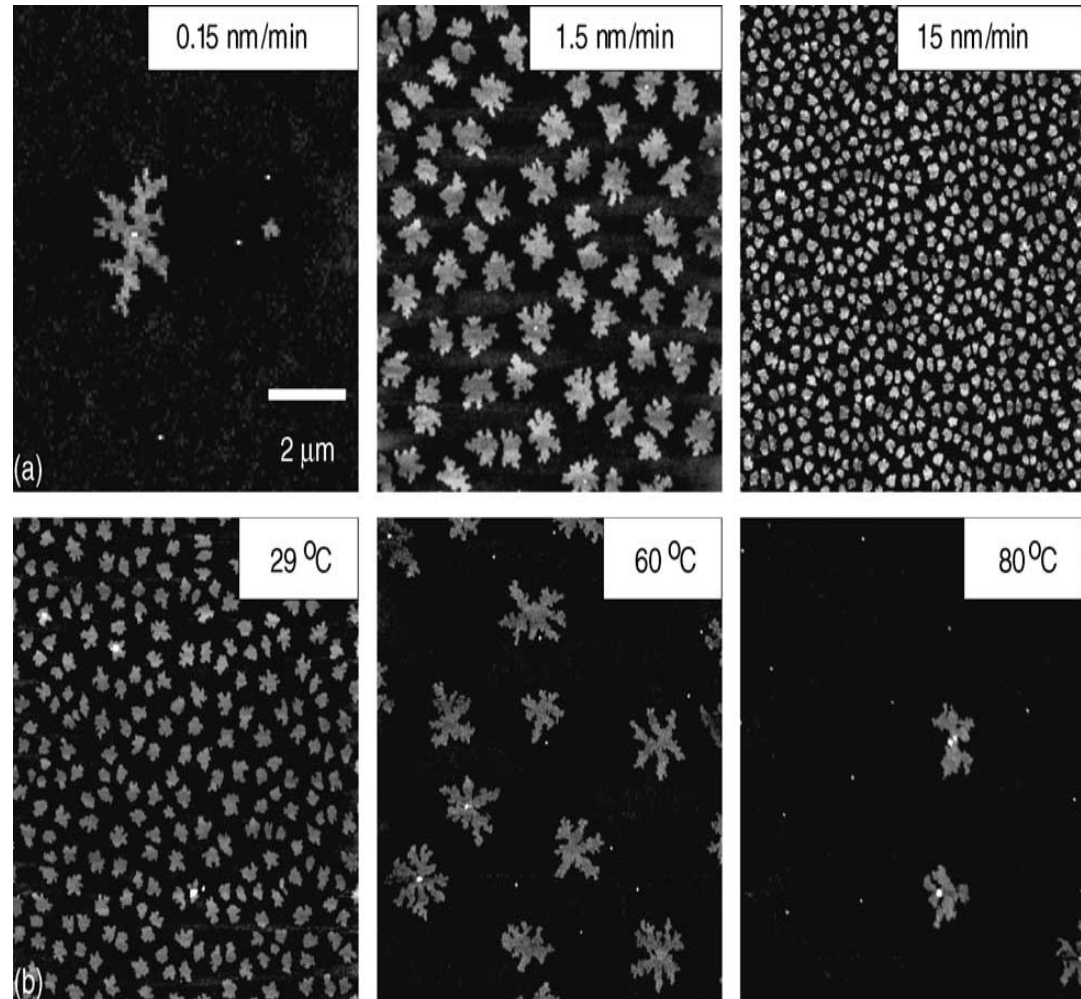
Multiple domains-disorder



Example 1: Pentacene on SiO₂

Experimental details:

- Si wafer with 200nm thick SiO₂ layer(roughness < 0.1nm)
- Pentacene evaporated from fused quartz crucible
- Film thickness, 0.5nm
- Base pressure ~ 10⁻⁷ mbar
- Substrate temperature, T_s ~ 338K
- Deposition rate ~ 0.45nm/min

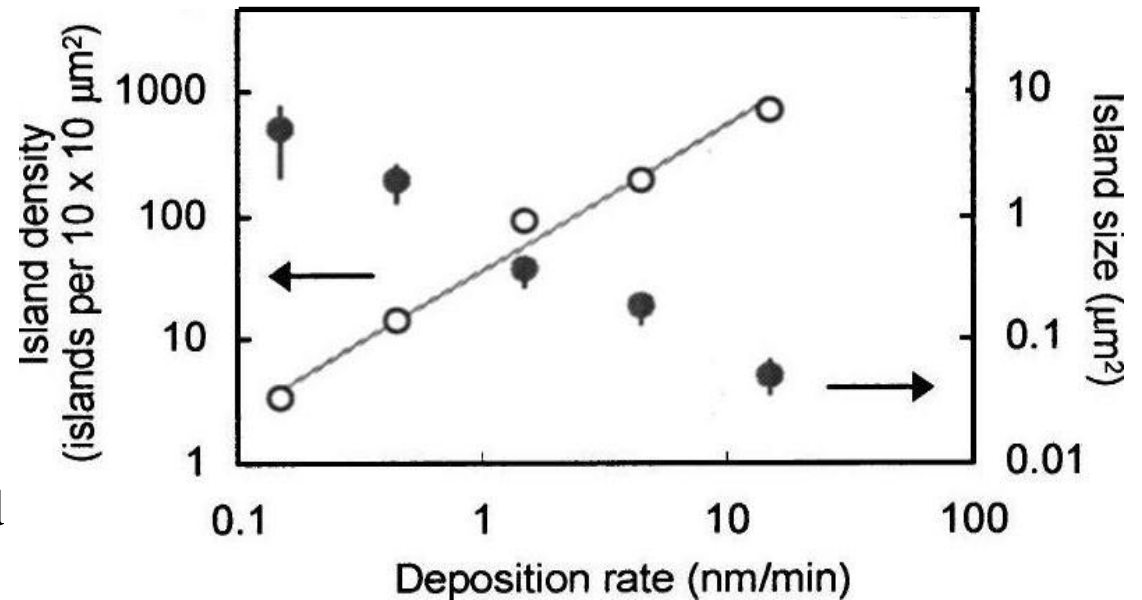


Effect of deposition rate

- Morphology of island becomes compact
- No. density of island increases


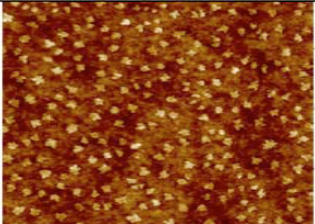
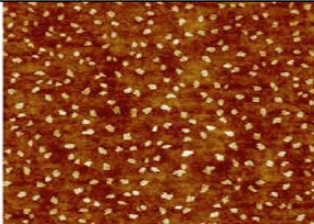
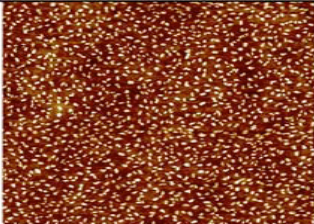

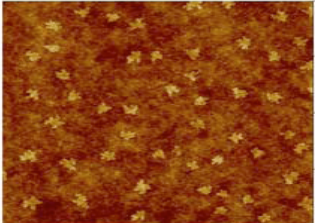
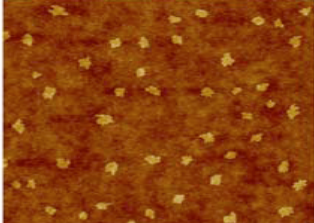
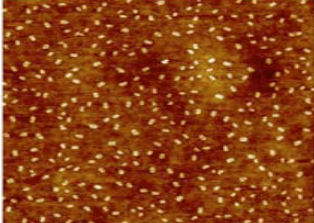

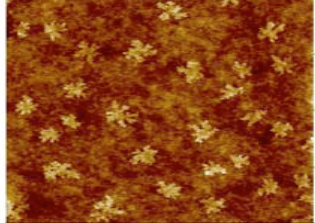
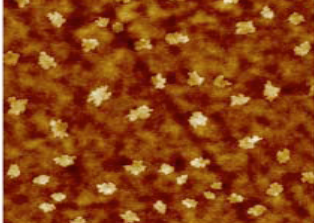
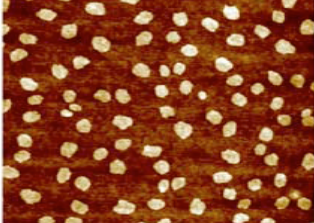

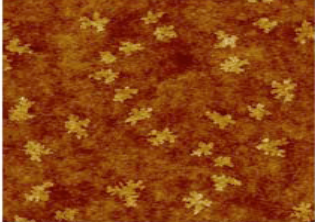
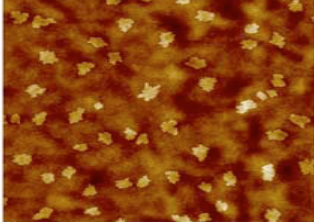
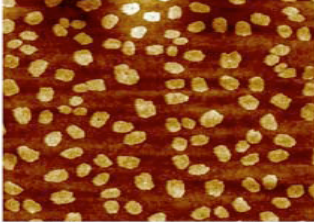
Effect of T_s

- Density N decreases by a few orders of magnitude as T_s increased from 29°C to 80°C

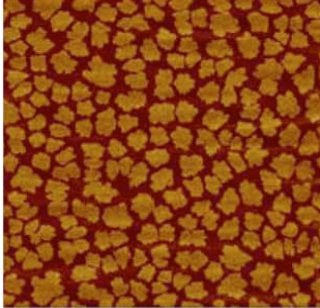
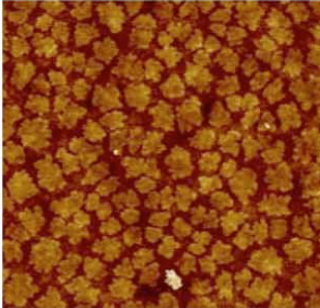
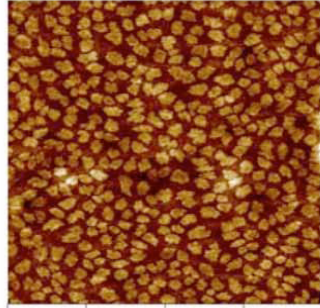
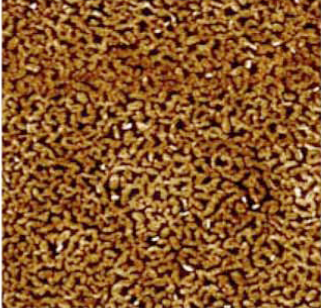
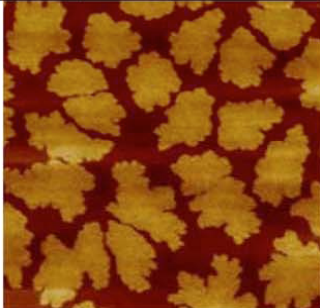
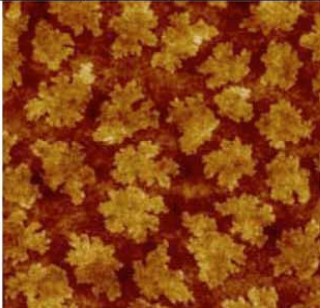
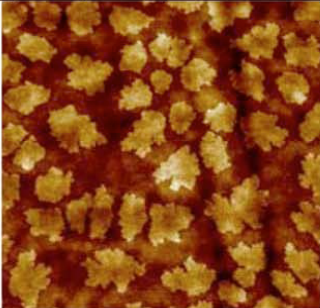
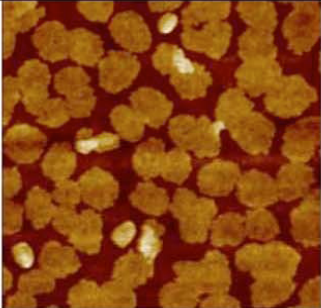
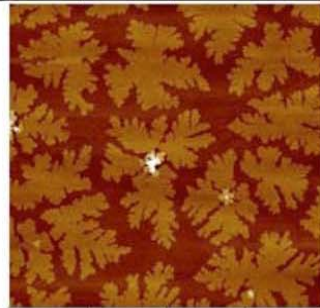

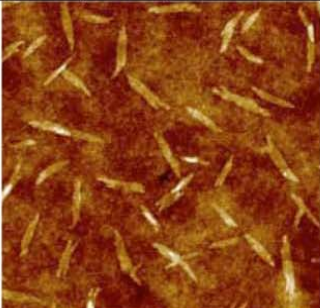
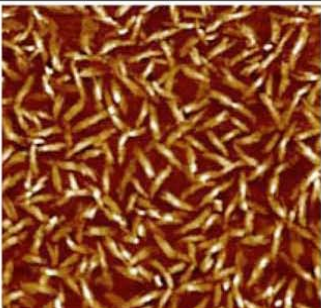


Conclusion: Nucleation density of islands can be tuned by both deposition rate and substrate temperature

Example 2: AFM images of Pentacene (0.2 ML) thick on different substrates

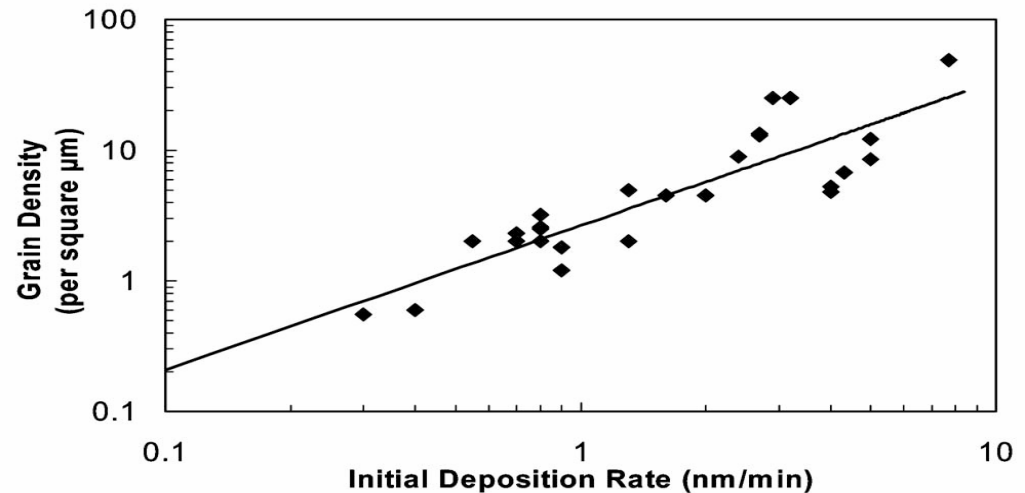
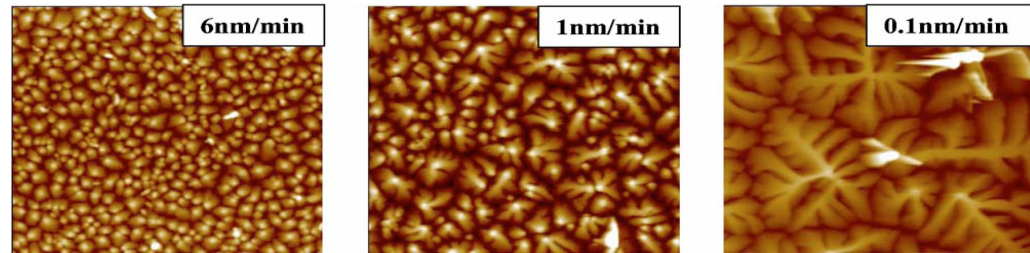
	SiO ₂	PVP	PVCi	PMMA
25°C	 <p>1st ML coverage: 15% mean grain area: 0.075 μm^2 grains per 100μm^2: 192</p>	 <p>1st ML coverage: 16% mean grain area: 0.056 μm^2 grains per 100μm^2: 250</p>	 <p>1st ML coverage: 11% mean grain area: 0.033 μm^2 grains per 100μm^2: 317</p>	 <p>1st ML coverage: 19% mean grain area: 0.012 μm^2 grains per 100μm^2: 1534</p>
60°C	 <p>1st ML coverage: 7% mean grain area: 0.147 μm^2 grains per 100μm^2: 42</p>	 <p>1st ML coverage: 6% mean grain area: 0.11 μm^2 grains per 100μm^2: 47</p>	 <p>1st ML coverage: 5% mean grain area: 0.106 μm^2 grains per 100μm^2: 47</p>	 <p>1st ML coverage: 8% mean grain area: 0.025 μm^2 grains per 100μm^2: 298</p>
65°C	 <p>1st ML coverage: 10% mean grain area: 0.405 μm^2 grains per 100μm^2: 24</p>	 <p>1st ML coverage: 10% mean grain area: 0.32 μm^2 grains per 100μm^2: 31</p>	 <p>1st ML coverage: 9% mean grain area: 0.19 μm^2 grains per 100μm^2: 45</p>	 <p>1st ML coverage: 19% mean grain area: 0.18 μm^2 grains per 100μm^2: 103</p>
70°C	 <p>1st ML coverage: 10% mean grain area: 0.331 μm^2 grains per 100μm^2: 29</p>	 <p>1st ML coverage: 9% mean grain area: 0.252 μm^2 grains per 100μm^2: 34</p>	 <p>1st ML coverage: 8% mean grain area: 0.146 μm^2 grains per 100μm^2: 51</p>	 <p>1st ML coverage: 19% mean grain area: 0.175 μm^2 grains per 100μm^2: 106</p>

Pentacene on different substrates

	SiO ₂	PVP	PVCi	PMMA
25°C 0.8ML	 <p>1st ML coverage: 52% mean grain area: 0.331 μm² grains per 100μm²: 142</p>	 <p>1st ML coverage: 47% mean grain area: 0.441 μm² grains per 100μm²: 97</p>	 <p>1st ML coverage: 43% mean grain area: 0.087 μm² grains per 100μm²: 303</p>	 <p>1st ML coverage: 81% m. grain area: coalescing grains per 100μm²: coal.</p>
65°C 0.8ML	 <p>1st ML coverage: 53% mean grain area: 2.94 μm² grains per 100μm²: 13</p>	 <p>1st ML coverage: 41% mean grain area: 1.62 μm² grains per 100μm²: 25</p>	 <p>1st ML coverage: 37% mean grain area: 0.518 μm² grains per 100μm²: 31</p>	 <p>1st ML coverage: 57% mean grain area: 1.026 μm² grains per 100μm²: coal.</p>
25°C 3.6ML	 <p>1st ML coverage: 100%</p>	 <p>1st ML coverage: 100%</p>	 <p>1st ML coverage: 100%</p>	 <p>1st ML coverage: 100%</p>

Transition from 2D to 3D- island growth

Film thickness ~ 33 ML
 $T_s = 25^\circ \text{C}$

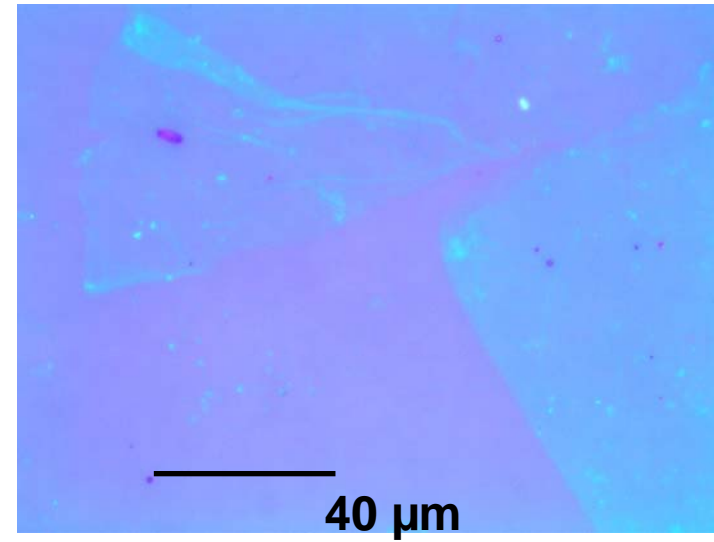
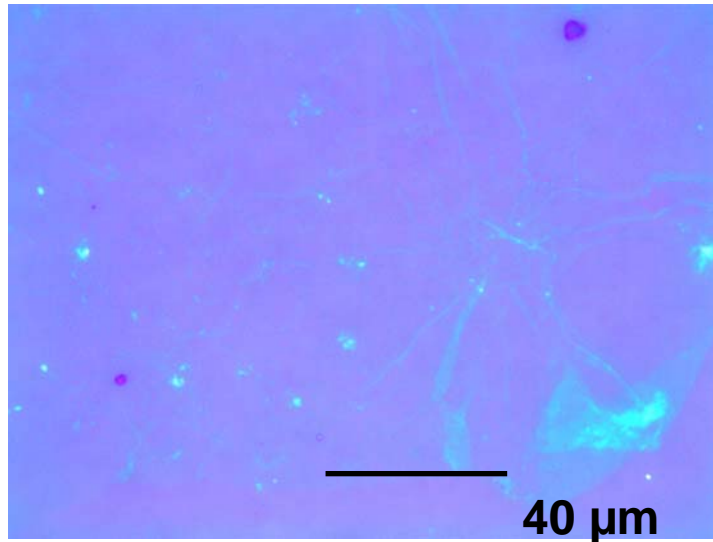


Conclusion: Pentacene growth on polymers is correlated
critical island size for substrates b/w $25-70^\circ \text{C}$ is $3 < i < 4$
Condensation is complete although reevaporation plays some role

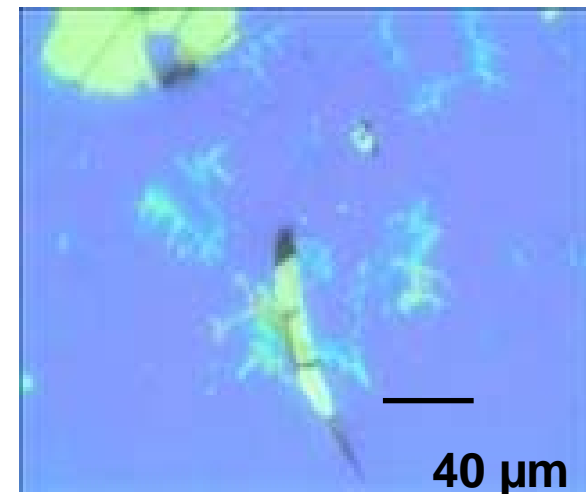
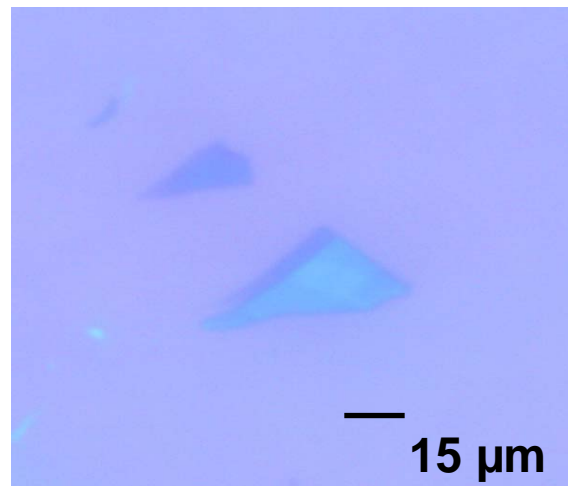
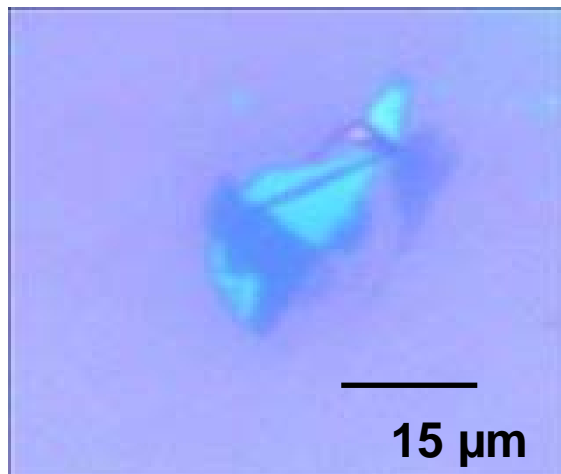
B. Stadlober et. al PRB B 74, 165302 (2006)

Optical microscope images of Graphene

Graphene prepared by CVD method



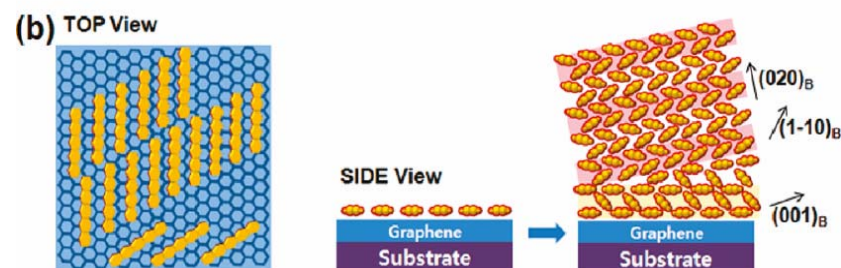
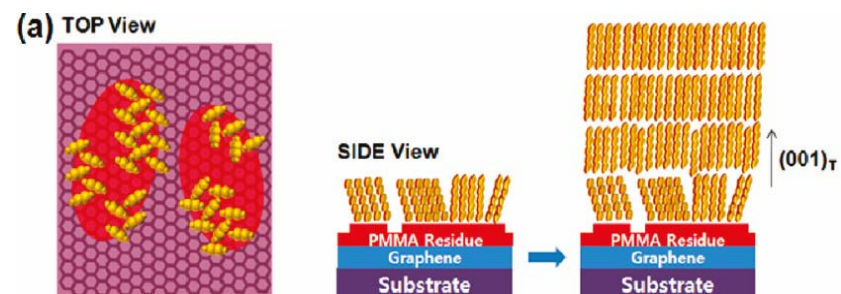
Graphene prepared by exfoliation



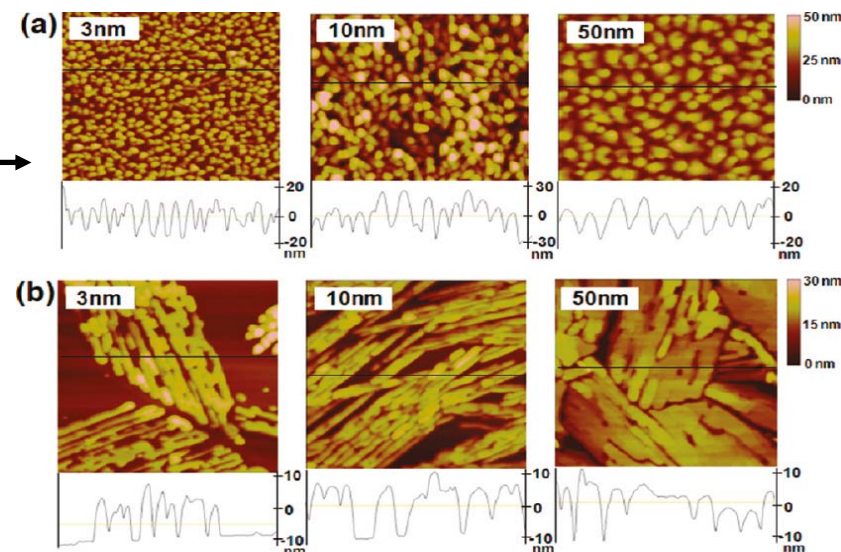
Pentacene on Graphene

- SiO₂ layer on Si wafer ~ 300 nm
- Pentacene deposition rate ~ 0.2 Å/ s

- a) Untreated graphene films
 b) Thermally treated graphene films



AFM images of pentacene films on graphene



Conclusions

- Graphene is an excellent 2D structure with unusual electronic and optical properties
- Organic semiconductors (OS) on substrates can be successfully grown in sub monolayer or more monolayer by OMBD
- AFM is an important tool to study initial stages of growth of organic semiconductor on substrates
- Graphene prepared by CVD and mechanical exfoliation methods can be used as a substrate